

IN THE CLAIMS:

1. (currently amended) A process for the production of a coated substrate comprising depositing a reflective metal layer ~~on to~~ onto a substrate by a low pressure deposition process performed in a coating atmosphere, ~~characterised in that~~ wherein the coating atmosphere contains a gaseous oxygen scavenger, ~~wherein when the reflective metal layer is deposited as a layer in a multilayer coating which also contains a bismuth oxide layer, said gaseous oxygen scavenger is not other than~~ hydrogen.

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2. (cancelled)

3. (previously amended) A process as claimed in claim 1 wherein each molecule of the gaseous oxygen scavenger is capable of combining with more than one atom of oxygen.

4. (previously amended) A process as claimed in claim 1 wherein the gaseous oxygen scavenger is a hydrocarbon.

5. (original) A process as claimed in claim 4 wherein the gaseous oxygen scavenger is a C₁ to C₄ hydrocarbon.

6. (original) A process as claimed in claim 5 wherein the gaseous oxygen scavenger is methane.

7. (previously amended) A process as claimed in claim 1 wherein the coating atmosphere contains the gaseous oxygen scavenger in an amount that is sufficient to alleviate oxidation and/or degradation of the reflective metal layer.

8. (previously amended) A process as claimed in claim 1 wherein the coating atmosphere contains a measurable amount of oxygen and contains the gaseous oxygen scavenger in an amount that exceeds 15 mol % of the amount of oxygen.

9. (original) A process as claimed in claim 8 wherein the coating atmosphere contains the gaseous oxygen scavenger in an amount that exceeds 30 mol % of the amount of oxygen.

10. (original) A process as claimed in claim 9 wherein the coating atmosphere contains the gaseous oxygen scavenger in an amount that exceeds 50 mol % of the amount of oxygen.

11. (previously amended) A process as claimed in claim 1 wherein the reflective metal layer is a silver layer.

12. (previously amended) A process as claimed in claim 1 wherein the reflective metal layer has a thickness in the range 5 to 30 nm.

13. (original) A process as claimed in claim 12 wherein the reflective metal layer has a thickness in the range of 7 to 18 nm.

14. (currently amended) A process as claimed in claim 1 wherein the reflective metal layer has a sheet resistance which ~~of the reflective metal layer~~ is below 12 Ω / square.

15. (currently amended) A process as claimed in claim 1 wherein the coating atmosphere contains a measurable amount of oxygen and the ~~sheet resistance of the reflective metal layer deposited in the coating atmosphere~~ has a sheet resistance which is below 12 Ω / square.

16. (original) A process as claimed in claim 15 wherein the sheet resistance of the reflective metal layer deposited in the coating atmosphere is below 8 Ω / square.

17. (previously amended) A process as claimed in claim 1 wherein the low pressure deposition process for depositing the reflective metal layer is sputtering.

18. (currently amended) A process for the production of a coated substrate as claimed in claim 1 that additionally comprises depositing a metal oxide anti-reflection layer by a low pressure deposition process before depositing the reflective metal layer.

19. (cancelled)

20. (Amended) A process as claimed in claim 1 wherein the substrate is curved.

21-25. (cancelled)
